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Electrical Engineering & Computer Science, Massachusetts Institute of Technology, 6.2540 Course Project

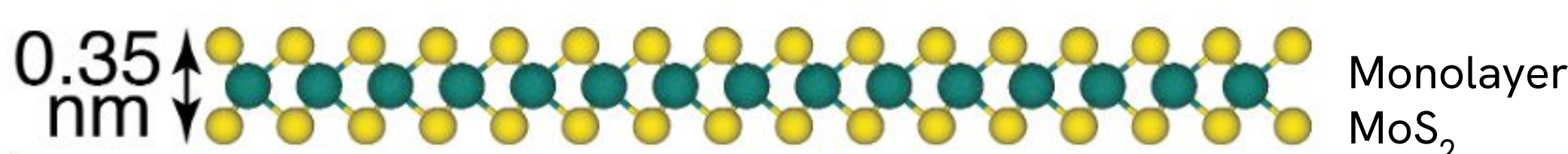
Introduction

Background:

- Approaching the end of Moore's law
 - Shrinking traditional silicon transistors to improve performance is getting harder because of quantum tunnelling
- 2D materials
 - Diverse functionality
 - Better electronic properties
 - Allow for flexible form factors

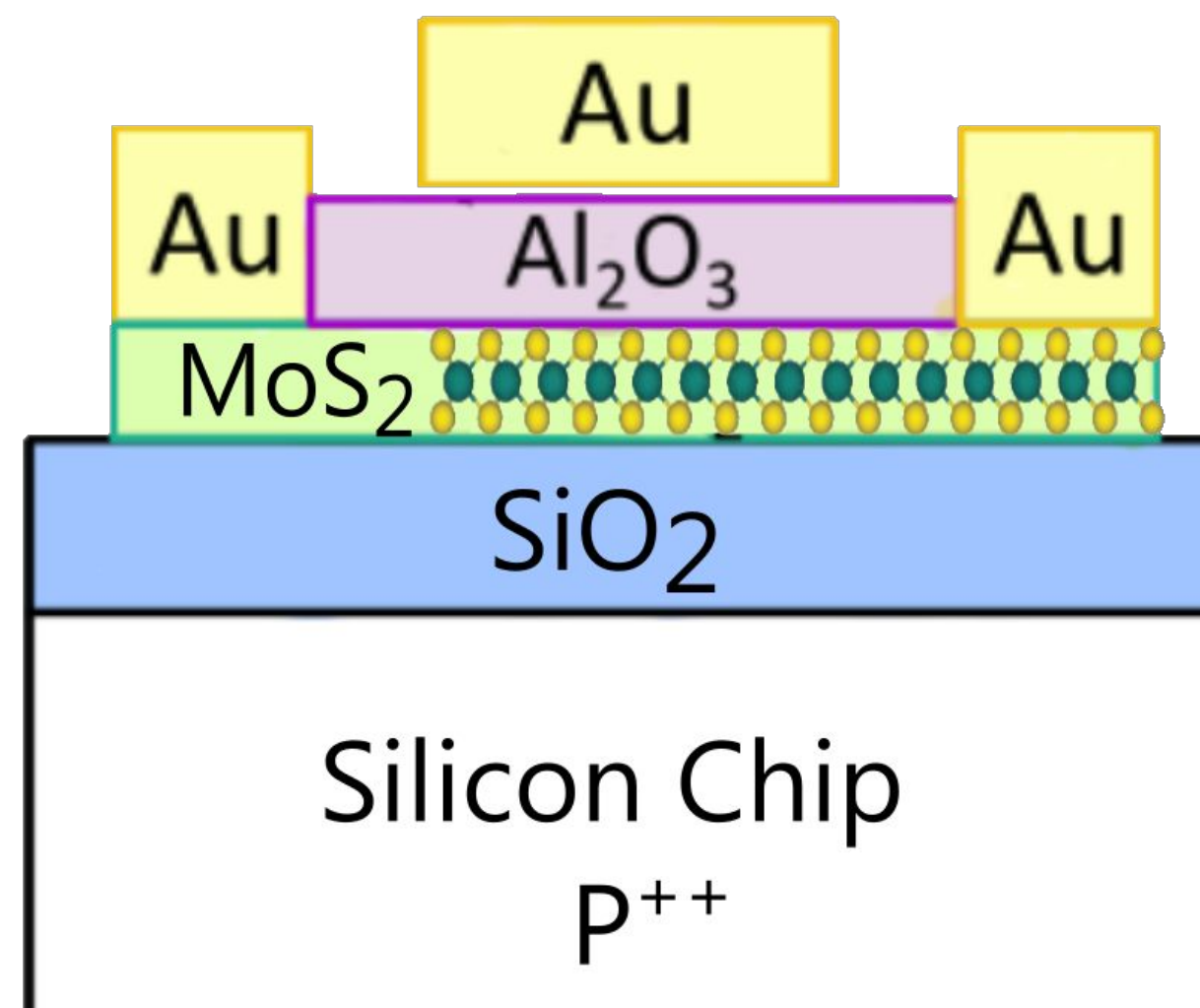
Goal:

- Fabricate a MOSFET using MoS₂ instead of Si
- Implement a top-gate approach
- Characterize transistor performance



Design

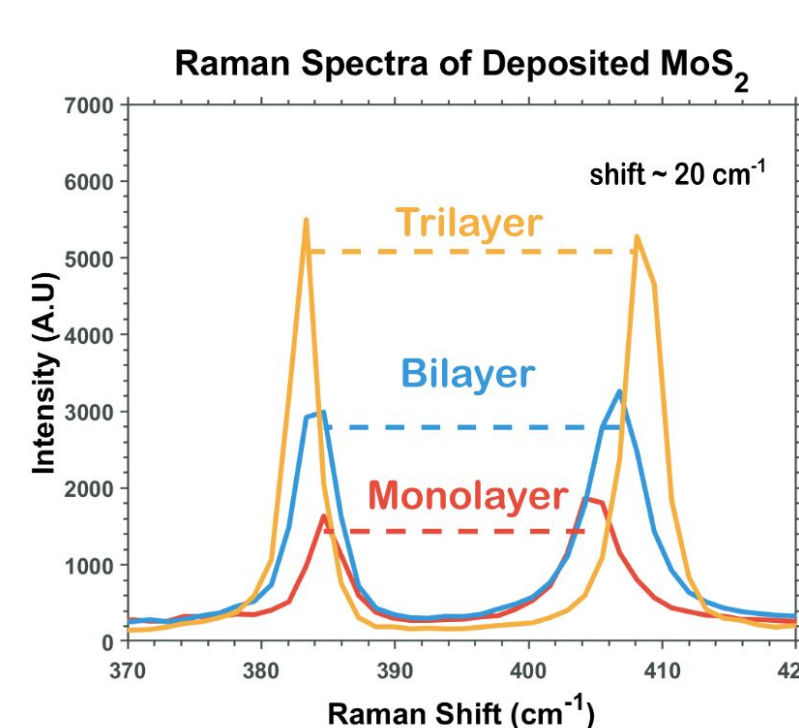
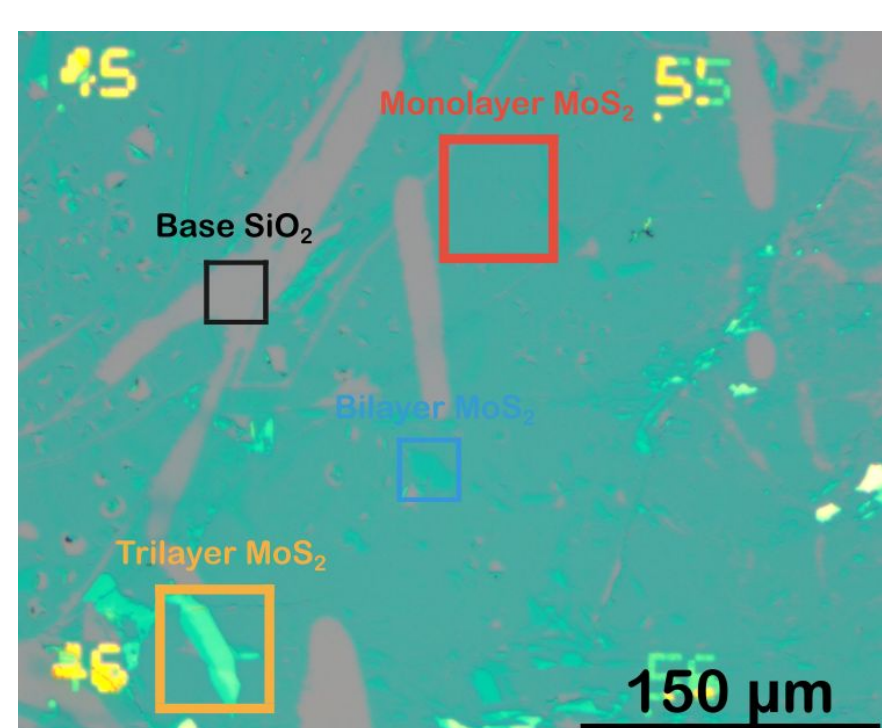
- Silicon base
- MoS₂ channel
- Al₂O₃ oxide
- Gold electrodes and traces
- 20 nm and 30 nm oxide thickness
- 3 μm channel length
- Vary channel width



MoS2 Transistor Fabrication

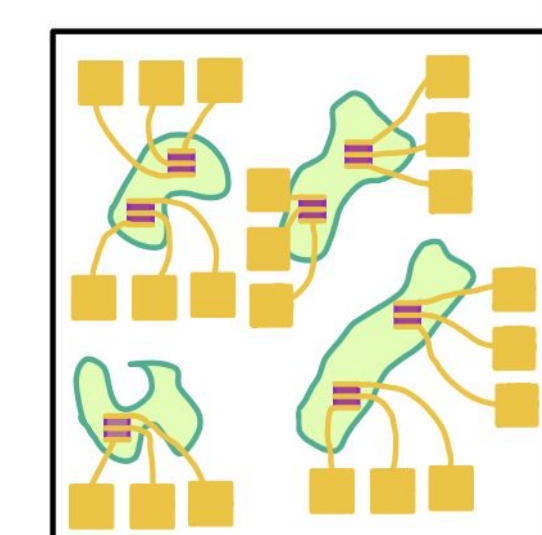
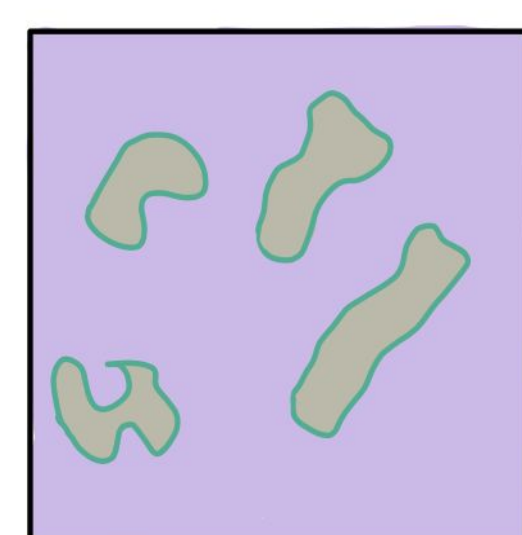
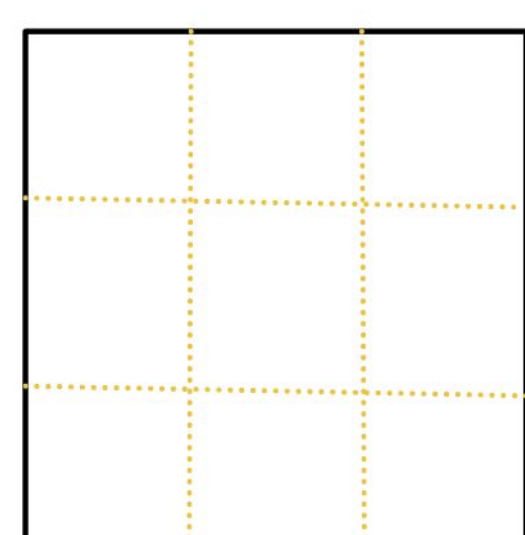
Gold-Mediated MoS2 exfoliation

- Van Der Waals interactions from special polymer is good for picking up large monolayer patches
- Contiguous patches ~100 μm in each dimension
- Monolayer, Bilayer, and Trilayer patches

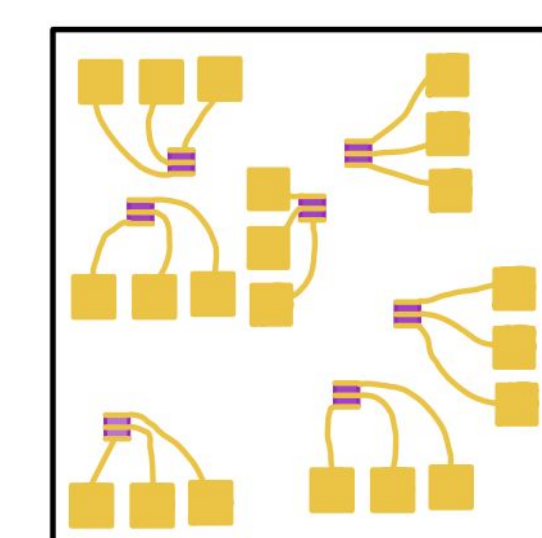
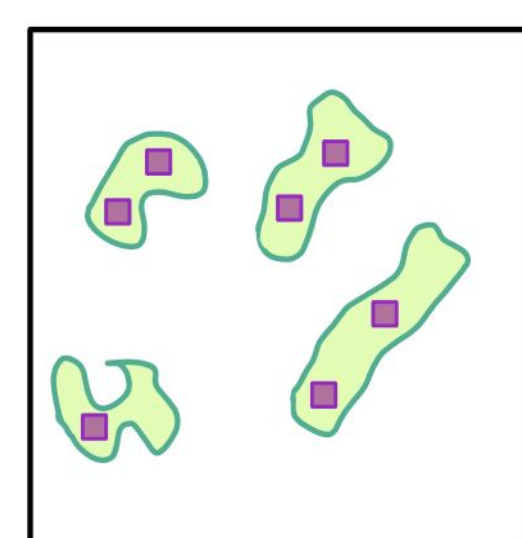
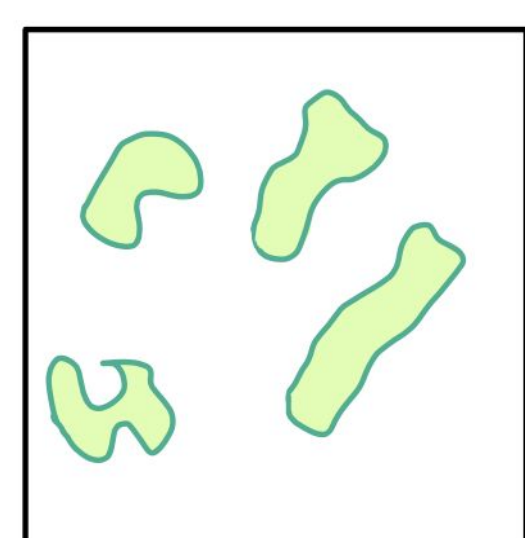


KLayout to generate Lithography Masks

- 1.5 μm oxide tolerance
- 2 μm source/drain and gate distance
- 20 μm traces
- 300x300 μm contact pads

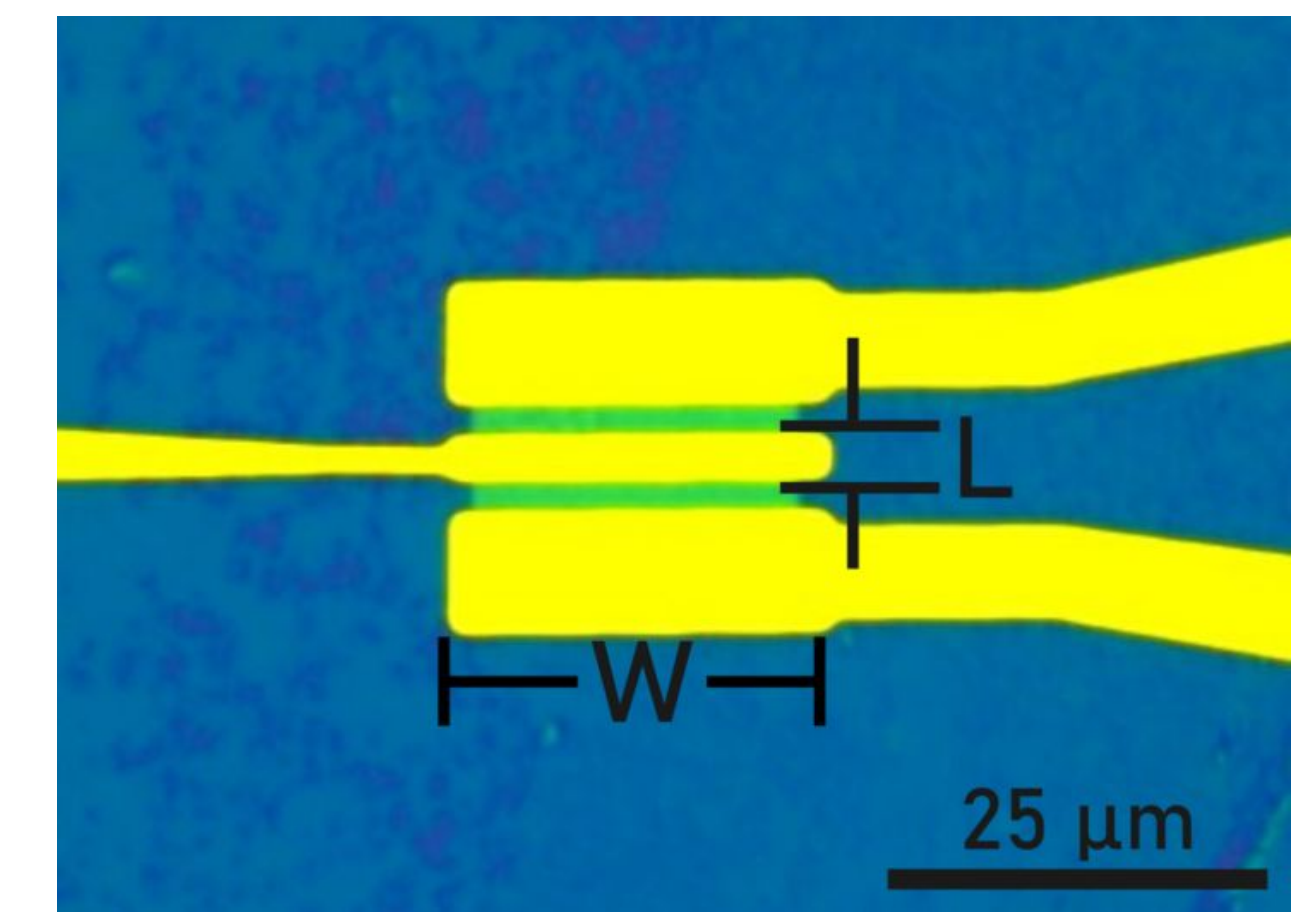
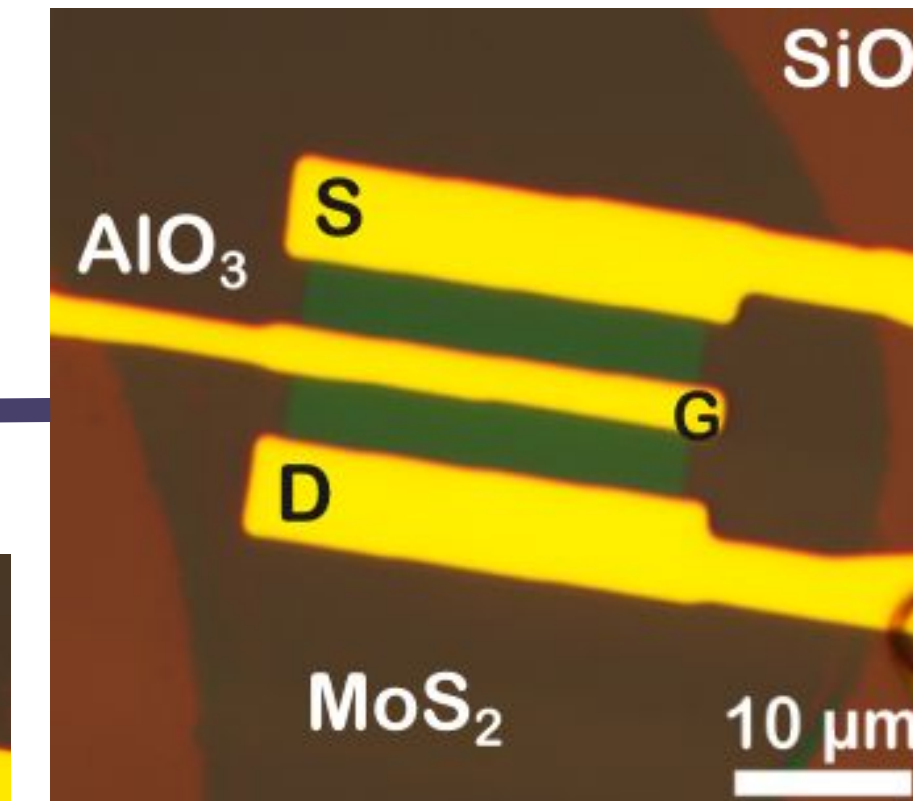
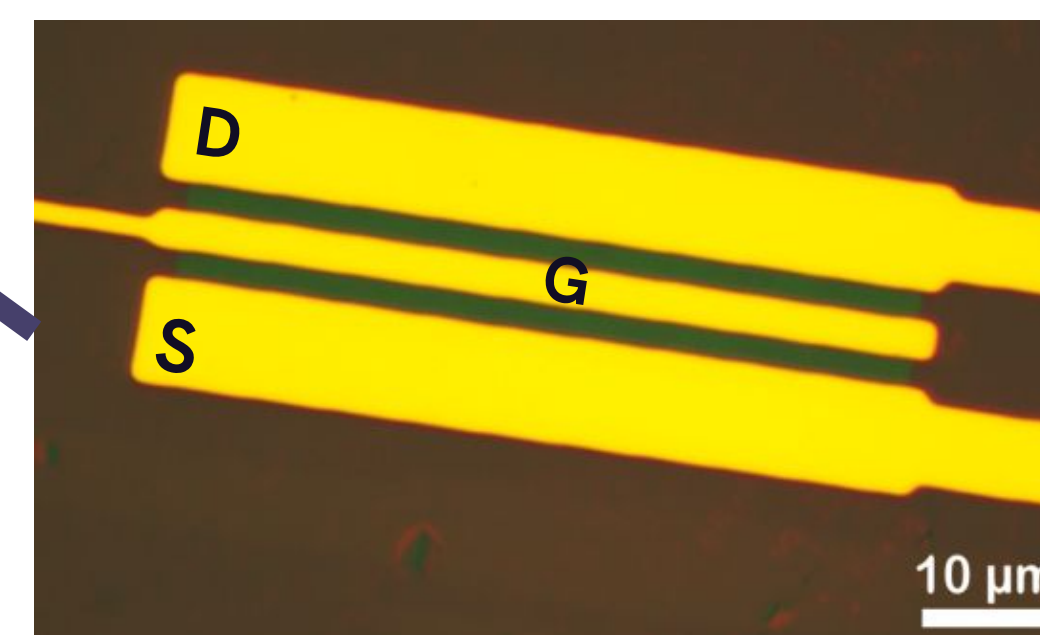
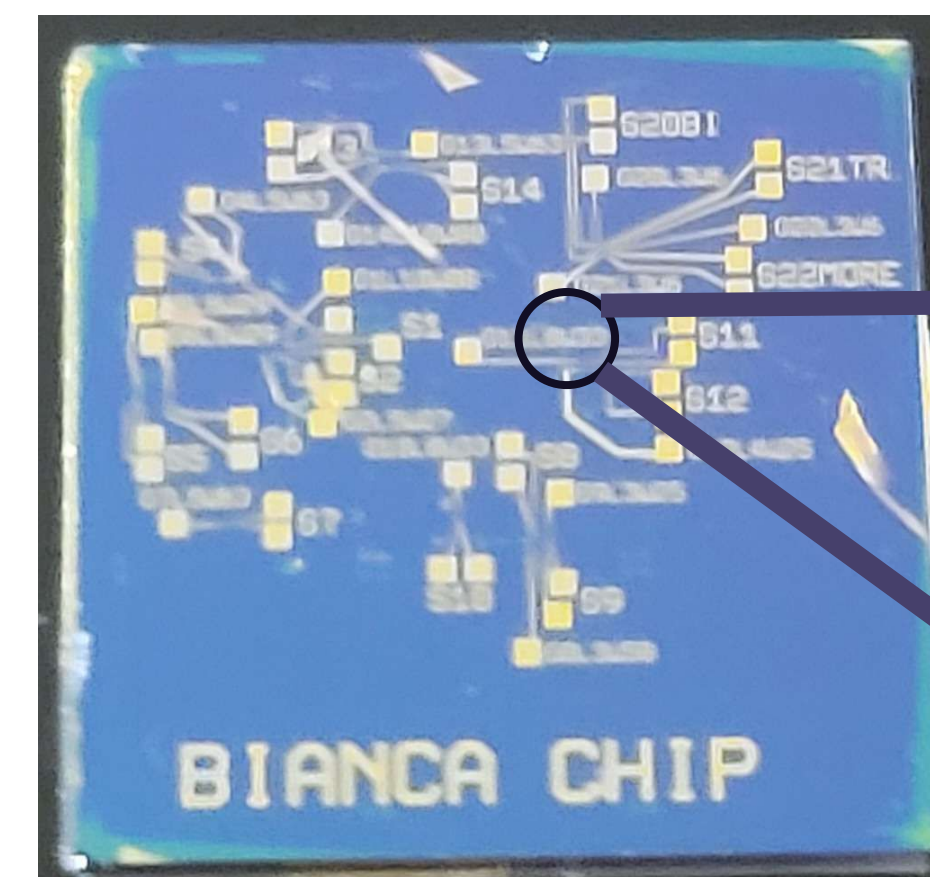


1. Original substrate 3. ALD Deposition 5. Electrodes

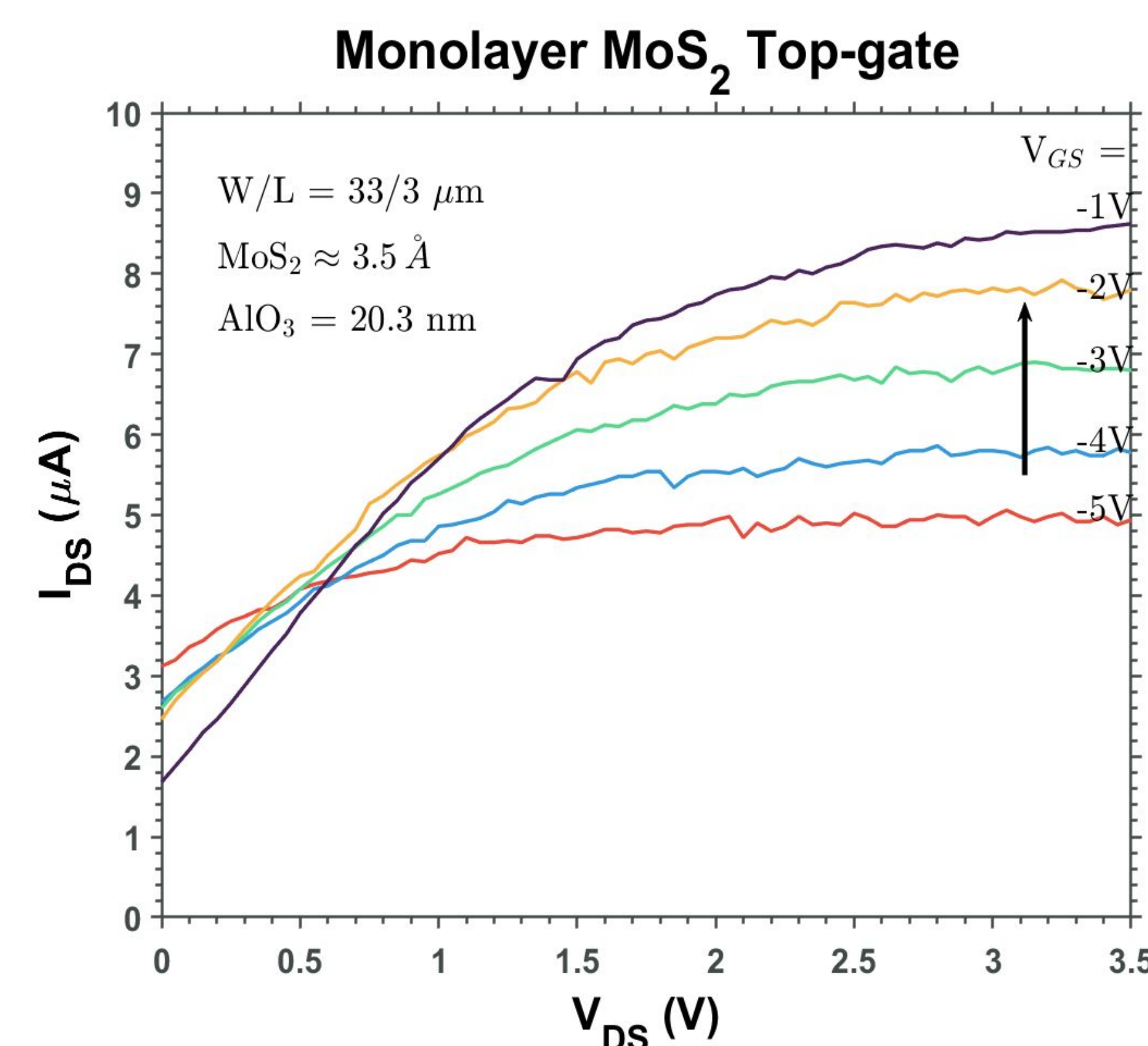


2. MoS2 Exfoliation 4. Oxide Lithography 6. MoS2 Etching

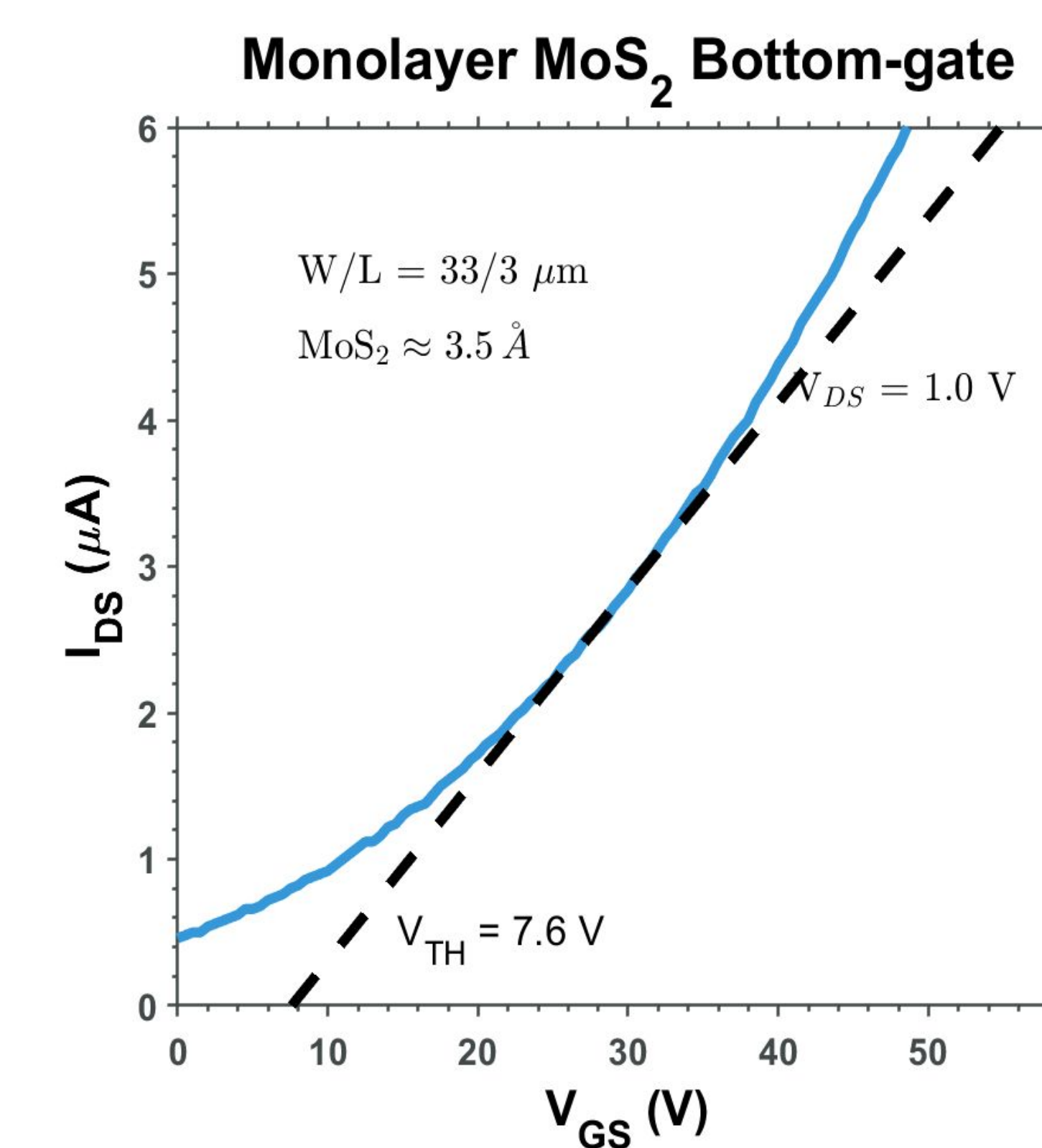
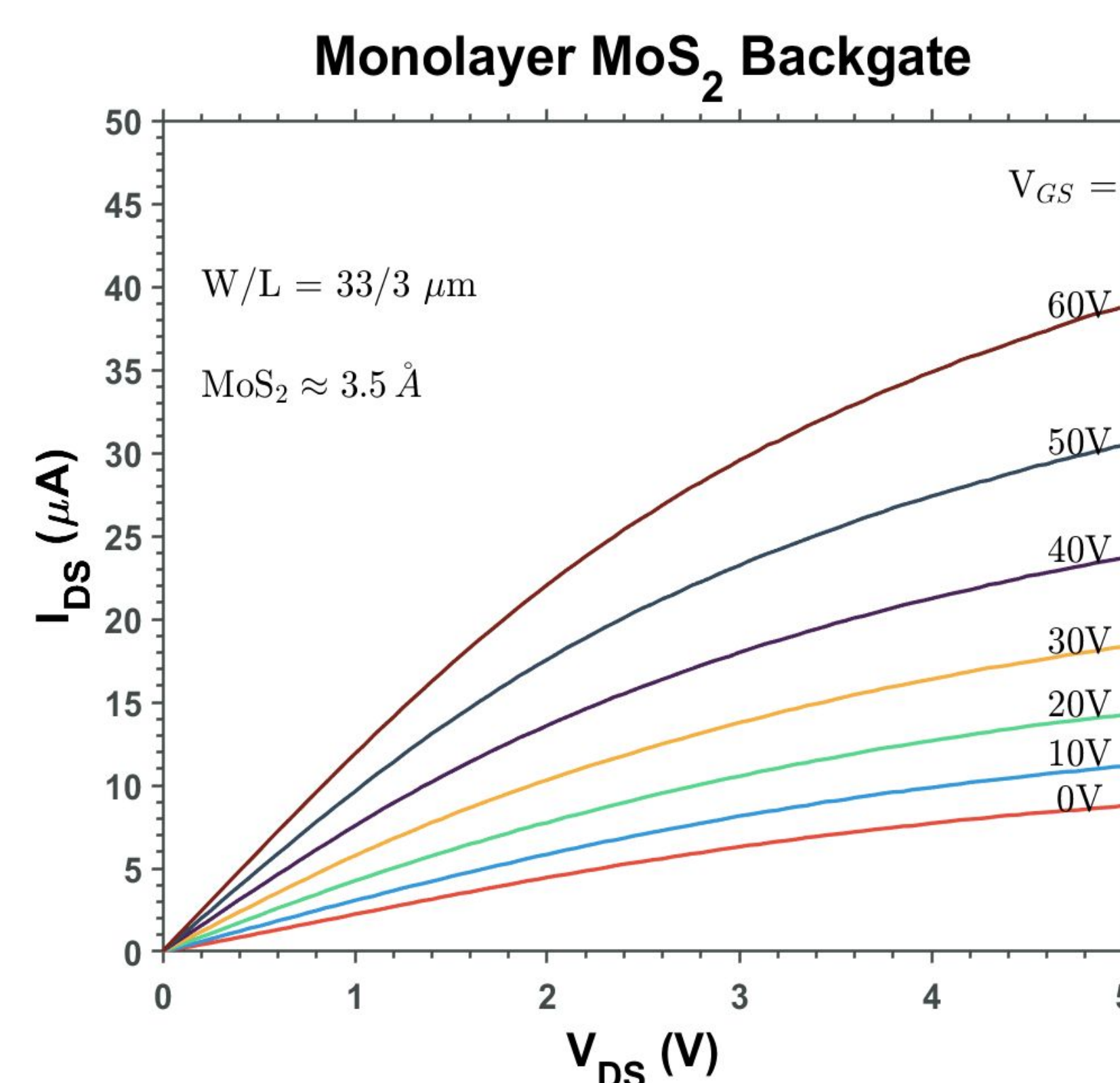
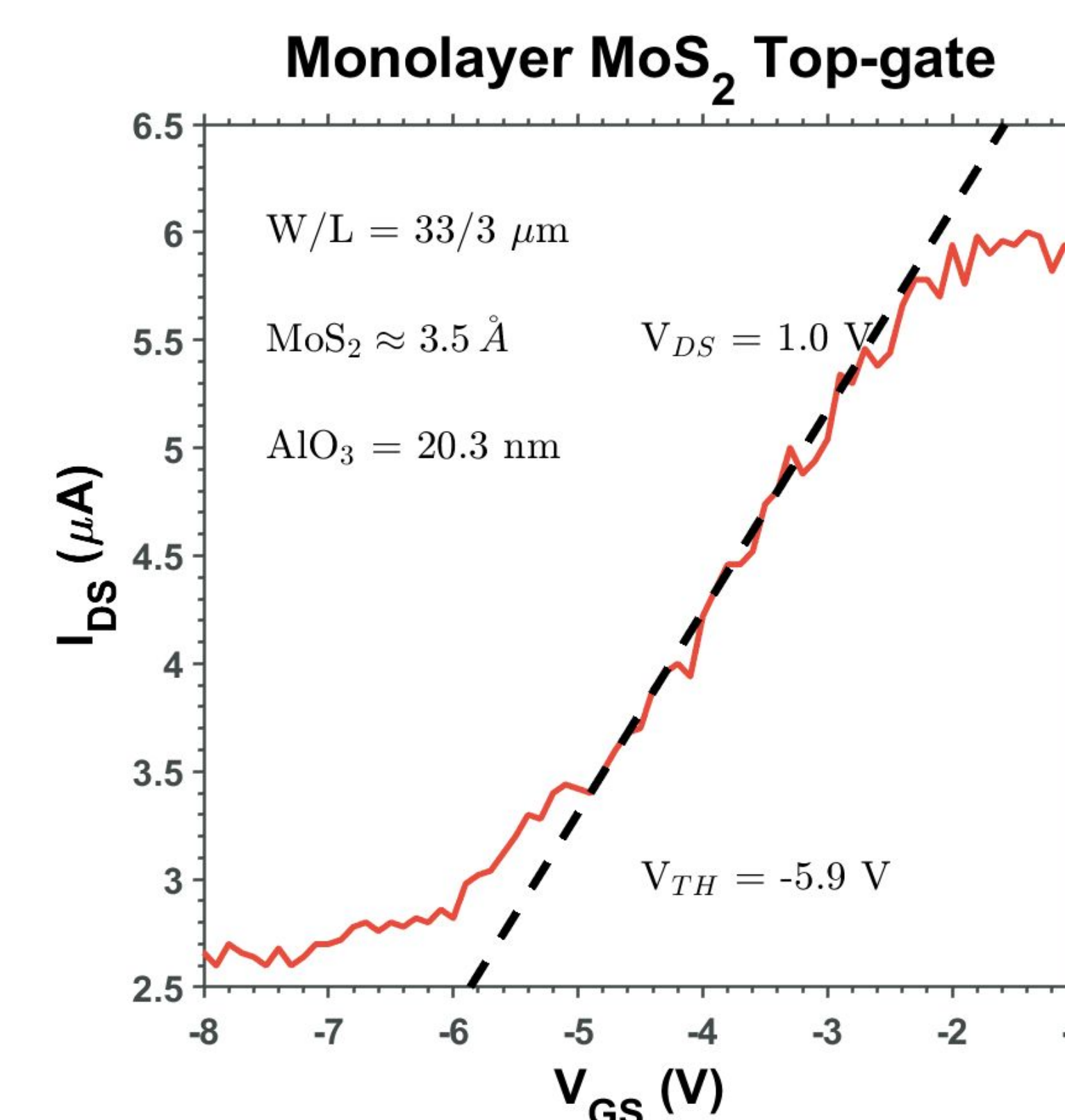
Results



Output Characteristic



Transfer Characteristics



Theoretical Topgate Saturation Current

$$V_T = V_{FB} + 2\psi_p + \frac{1}{C_{ox}} \sqrt{2\epsilon_s q N_D (2\psi_p)}$$

$$C_{ox} = \frac{\epsilon_0 \epsilon_x}{t_{ox}}$$

$$= 7.3 * 8.85 * 10^{-12} / (20 * 10^{-9}) = 0.0032$$

$$I_{ds} = \mu_{sat} C_{ox} \frac{W}{2L} (V_{TH} - V_{GS})^2$$

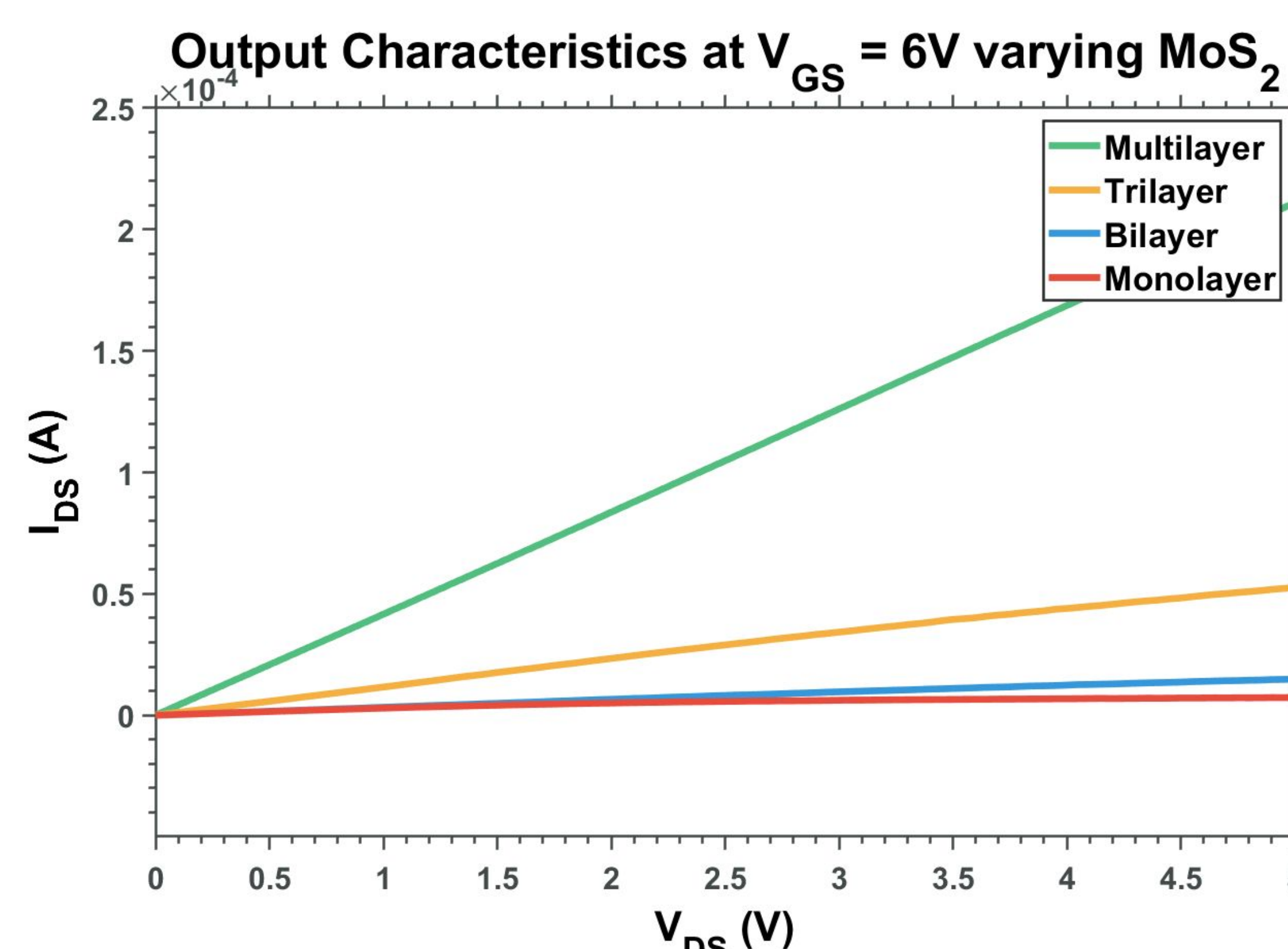
$$= 105 * 0.0032 * 33/6 * (V_{GS} - (5.9))^2$$

For $V_{GS} = -1$ V \rightarrow 44 A
For $V_{GS} = -4$ V \rightarrow 6.7 A

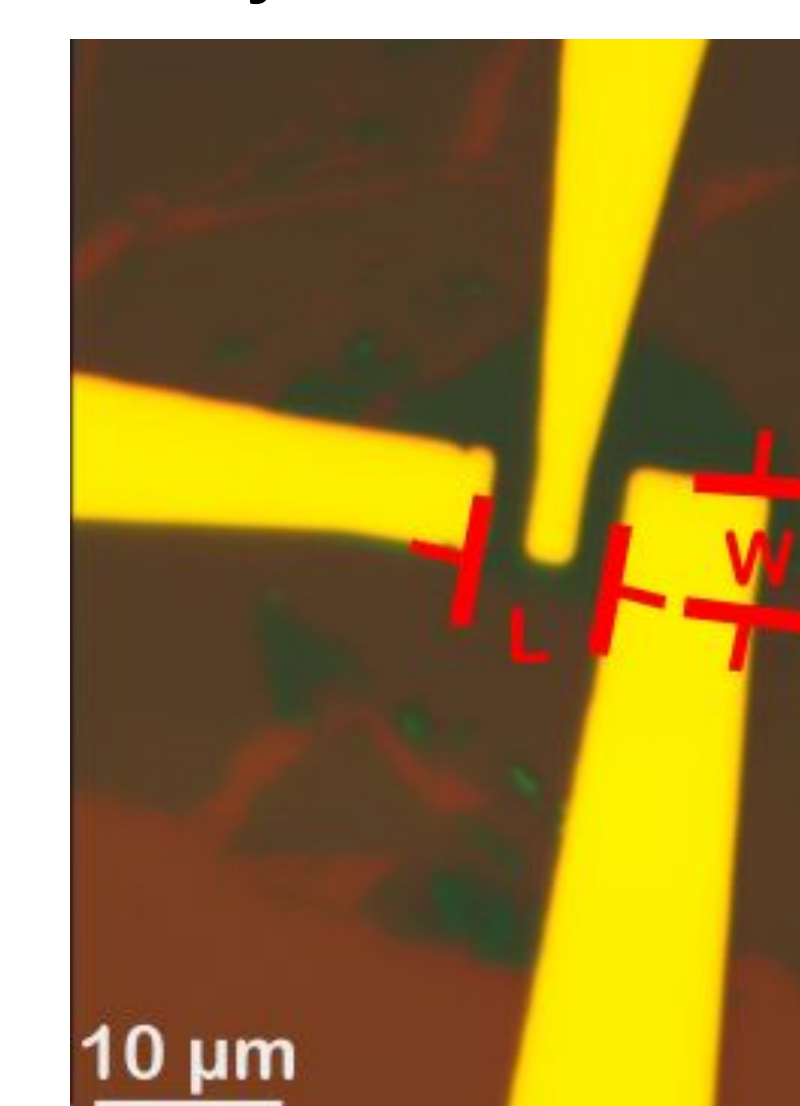
- We had dozens of transistors across 4 chips
 - Presented are samples from chip B
- Back gate and Top gate results are as expected for an NMOS transistor
- Threshold voltages are calculated and drawn on the graphs
- Results are very promising



Multi-layer MoS2



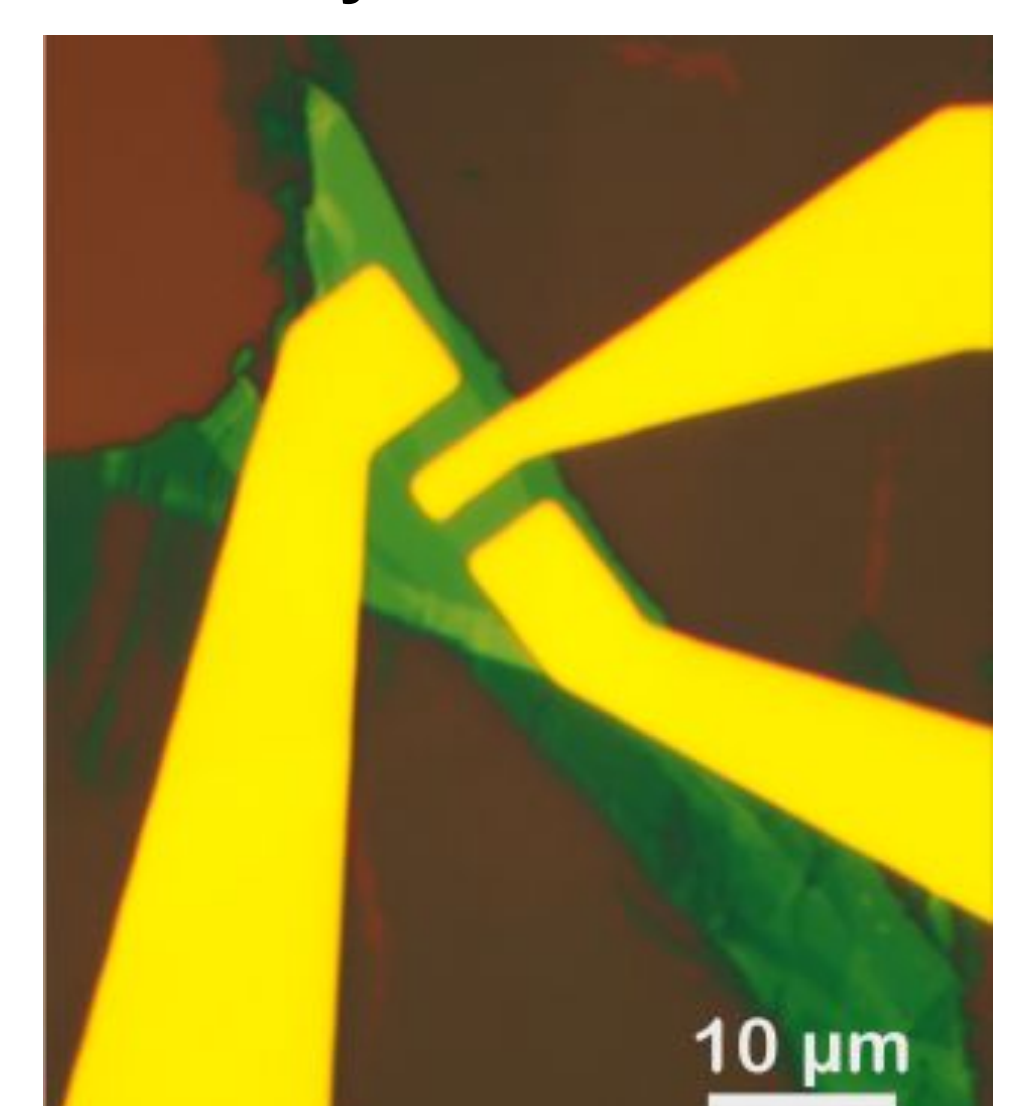
Bi-Layer



Tri-Layer



Multi-Layer



Acknowledgements

6.2540 Staff



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References

- Radisavljevic, B., Radenovic, A., Brivio, J. *et al.* Single-layer MoS₂ transistors. *Nature Nanotech* 6, 147–150 (2011). <https://doi.org/10.1038/nnano.2010.279>
- Gold mediated MoS₂ figure from S1.15 of last years conference
- All other figures are drawn or generated by the authors